

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applic. No. : 10/723,631 ✓ Confirmation No. 9710  
Applicant : Frank-Michael Kamm  
Filed : November 26, 2003 ✓  
Title : REFLECTION MASK FOR PROJECTING A STRUCTURE  
ONTO A SEMICONDUCTOR WAFER AND METHOD FOR  
PRODUCING THE MASK  
Group Art Unit : 1756  
Examiner : Stephen D. Rosasco  
Docket No. : P2002,1010  
Customer No. : 24131

DECLARATION UNDER 37 C.F.R. § 1.131

I, Frank-Michael Kamm, the inventor of the invention described and claimed in the instant application hereby declare that:

The invention of the above-identified application was "conceived" in Germany, a WTO member country, at least as early as July 5, 2002. The invention was "reduced to practice" at least as early as November 28, 2002, through the filing of a patent application in Germany.

I personally completed an Invention Disclosure (*Erfindungsmeldung*) on July 5, 2002, and then submitted it to my supervisor, Mr. Gerd Unger at the <sup>Infineon</sup> ~~Siemens~~ department MH D, who confirmed receipt on July 8, 2002. Enclosed, as corroborating evidence is the Invention Disclosure (*Erfindungsmeldung*).

I hereby declare that all statements made herein of my own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under 18 U.S.C. § 1001 and such willful false statements may jeopardize the validity of the application or any patent issued thereon.

Frank-Michael Kamm May 17, 2006  
Frank-Michael Kamm Date